IV. AMENDMENTS TO THE CLAIMS

1. (CURRENTLY AMENDED) An optical recording medium which comprises at least a recording layer comprising an organic dye, a reflecting layer composed of a metal, and a protective layer laminated in this order on a light-transmittable substrate, wherein a groove pitch is not less than 0.6 μm and less than 1.0 μm,

wherein the reflecting layer is a thin film comprising silver as the major component and satisfying a relative intensity ratio of I(200)/I(111) being 0.49 or more when an X-ray diffraction intensity by a (111) plane is designated as I(111) and an X-ray diffraction intensity by a (200) plane is designated as I(200) in an X-ray diffraction spectrum measured by a θ-2θ method while an angle of incidence with reference to a surface of the light-transmittable substrate is set at θ.

2. (ORIGINAL) The optical recording medium according to claim 1, wherein a depth of a groove formed on the light-transmittable substrate is from 150 to 200 nm, and a width of the groove is from 0.2 to 0.4 μm.

3. (CANCELED).

4. (CURRENTLY AMENDED) The optical recording medium according to any one of claims 1 ~~to 3~~ and 2, wherein the organic dye in the recording layer is an azo type dye and/or a cyanine type dye.

5. (CURRENTLY AMENDED) A method for producing an optical recording medium which comprises at least a recording layer comprising an organic dye, a reflecting layer composed of a metal by a sputtering method, and a protective layer laminated in this order on a light-transmittable substrate, wherein a groove pitch is not less than 0.6 μm and less than 1.0 μm,

said method comprising the step of forming a thin film comprising silver as the major component and satisfying a relative intensity ratio of I(200)/I(111) being 0.49 or more when an X-ray diffraction intensity by a (111)

plane is designated as I(111) and an X-ray diffraction intensity by a (200) plane is designated as I(200) in an X-ray diffraction spectrum measured by a θ-2θ method while an angle of incidence with reference to a surface of the light-transmittable substrate is set at θ, by controlling a sputtering gas pressure in a sputtering chamber in forming the reflecting layer by the sputtering method.

6. (CURRENTLY AMENDED) A method for producing an optical recording medium which comprises at least a recording layer comprising an organic dye, a reflecting layer composed of a metal by a sputtering method, and a protective layer laminated in this order on a light-transmittable substrate, wherein a groove pitch is not less than 0.6 μm and less than 1.0 μm,

said method comprising the step of forming a thin film comprising silver as the major component and satisfying a relative intensity ratio of I(200)/I(111) >0.47 when an X-ray diffraction intensity by a (111) plane is designated as I(111) and an X-ray diffraction intensity by a (200) plane is designated as I(200) in an X-ray diffraction spectrum measured by a θ-2θ method while an angle of incidence with reference to a surface of the light-transmittable substrate is set at θ, by controlling a sputtering gas pressure in a sputtering chamber in forming the reflecting layer by the sputtering method, wherein the sputtering gas pressure in the sputtering chamber is set within a range from a 0.23 to 0.53 Pa.